

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): F. ISSHIKI, et al

Serial No.: Not yet assigned

Filed: September 25, 2003

For: LASER INTERFEROMETER DISPLACEMENT MEASURING  
SYSTEM, EXPOSURE APPARATUS, AND ELECTRON BEAM  
LITHOGRAPHY APPARATUS

**LETTER CLAIMING RIGHT OF PRIORITY**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

September 25, 2003

Sir:

Under the provisions of 35 USC 119 and 37 CFR 1.55, applicants hereby claim  
the right of priority based on:

**Japanese Application No. 2000-089556  
Filed: March 28, 2000**

A Certified copy of said application document was filed in parent application  
Serial No. 09/818,713, filed March 28, 2001, said certified document filed in the United  
States Patent and Trademark Office on July 9, 2001. Acknowledge thereof is  
respectfully requested.

Respectfully submitted,



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Registration No. 29,621  
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CIB/jdc  
Enclosures  
703/312-6600

日本国特許庁  
PATENT OFFICE  
JAPANESE GOVERNMENT

別紙添付の書類に記載されている事項は下記の出願書類に記載されて  
いる事項と同一であることを証明する。  
This is to certify that the annexed is a true copy of the following application as filed  
with this Office.

出願年月日  
Date of Application:

2000年 3月28日

出願番号  
Application Number:

特願2000-089556

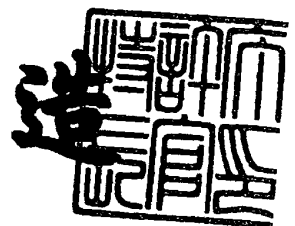
出願人  
Applicant(s):

株式会社日立製作所

2001年 4月13日

特許庁長官  
Commissioner,  
Patent Office

及川耕造



出証番号 出証特2001-303090